Docket No.: P2002,0645

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: FRANK-MICHAEL KAMM ET AL.

Filed : CONCURRENTLY HEREWITH

Title : REFLECTIVE MIRROR FOR LITHOGRAPHIC EXPOSURE AND

PRODUCTION METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

European Patent Application EP 1 065 532 A2 (Singh), dated January 3, 2001;

Morita, M. et al.: "Native Oxide Growth on Silicon Surface in Wet Ambient", Extended Abstract of the 22nd Conference on Solid State Devices and Materials, 1990, pp. 1063-1066;

Yasaka, T. et al.: "Layer-By-Layer Oxidation of Silicon", Materials Research Society Proc., Vol. 222, 1991, pp. 225-230;

Morita, M. et al.: "Control Factor of Native Oxide Growth on Silicon Surface in Air or in Ultrapure Water", Appl. Phys. Lett. 55 (6), American Institute of Physics, August 7, 1989, pp. 562-564.

Respectfully/submitted,

For Applicants

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Date: August 1, 2003

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FORM PTO-1449 (SUBSTITUTE)				Attorney Docket No.: P2002,0645 Appl. No.:						
U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				, (ppi. 110						
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